

HELMHOLTZ ZENTRUM

DRESDEN ROSSENDORF

#### <sup>1</sup> Helmholtz-Centre Dresden-Rossendorf, Dresden, Germany

# Caesium deposition on GaN to obtain a photocathode

### Method

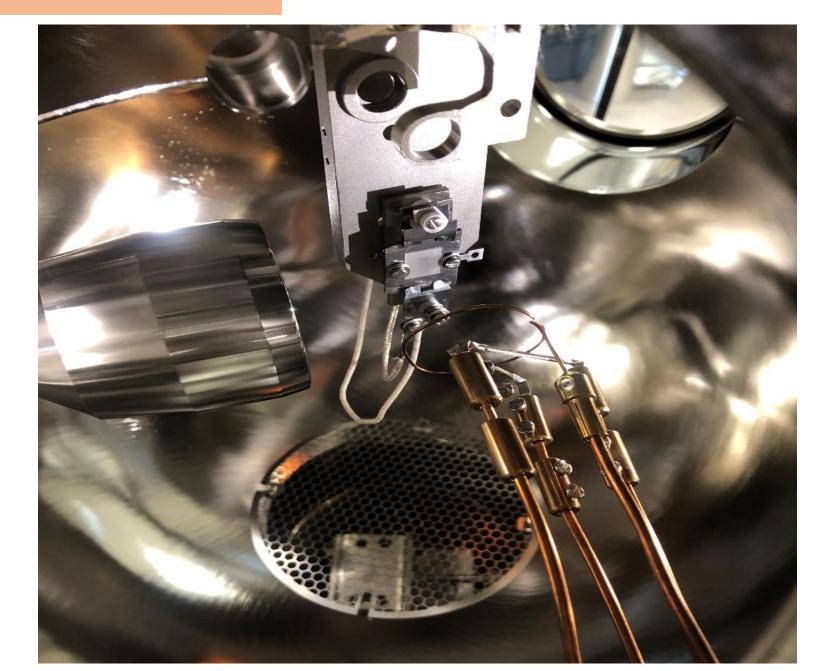


Fig. 1: experimental set-up inside of GaN UHV-chamber

- For first tests p-type GaN (with magnesium doping) on sapphire and later on silicon substrate is studied
- At first the sample is thermal cleaned
- Back at room-temperature the GaN is activated with a thin layer of caesium.
- Using the photoeffect, electrons from the activated GaN material are excited and ejected when illuminating the material with UV-light
- The released photoelectrons enter into the vacuum and are collected by a copper ring anode
- The number of released photoelectrons in ratio of the input photons of UV-light derives in the quantum efficiency (QE)

$$QE = \frac{N_{photonselectrons}}{N_{photonsofUV-light}}$$
 (1)

$$QE = \frac{h \cdot c}{q_e \cdot \lambda} \cdot \frac{I}{P_{UV-light}} \tag{2}$$

#### Results

- 1) Thermal treatment at certain temperature to desorb residual gases
- 2) deposition of caesium on GaN surface by using different caesium fluxes

Simultanously: detection of the photocurrent till saturation is reached

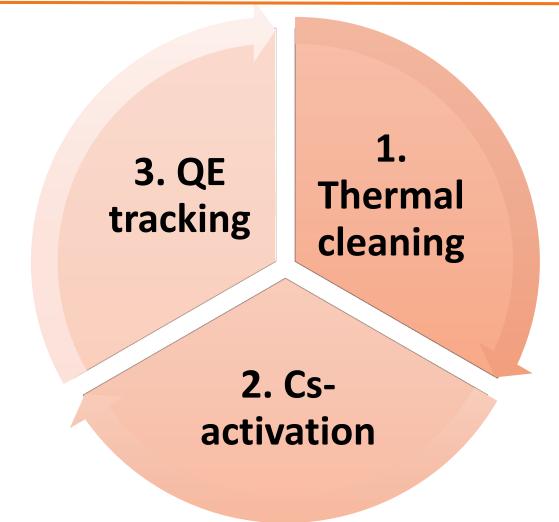


Fig. 2: scheme of cycle process

- 3) Tracking of the QE of the freshly prepared GaN:Cs photocathode over time till it drops nearly to zero
- 4) after degradation the material can thermal heated and activated again (re-activation)

#### GaN on silicon

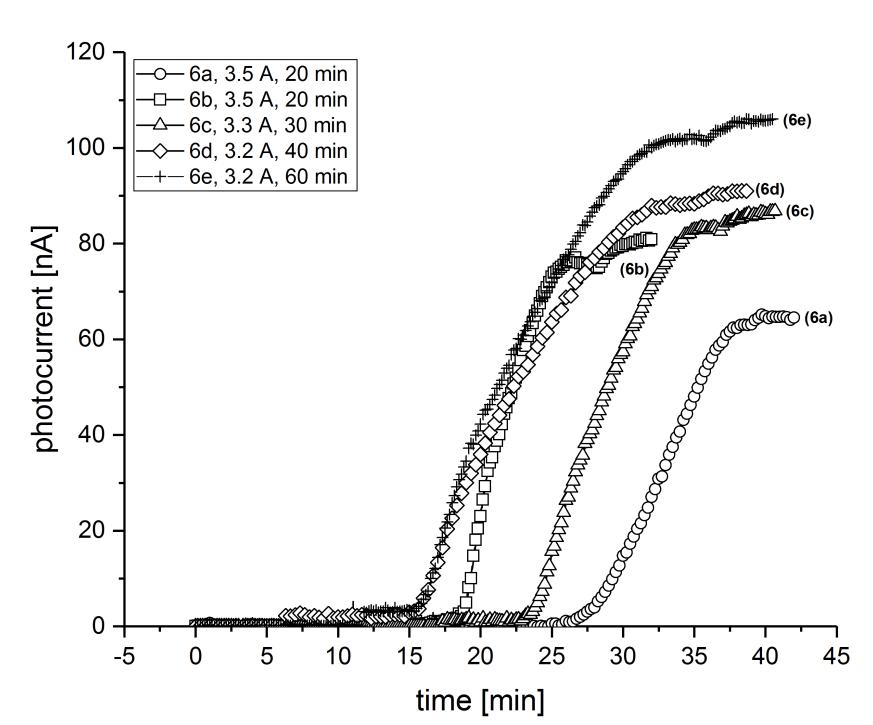


Fig. 3: photocurrent activation curves for GaN on silicon

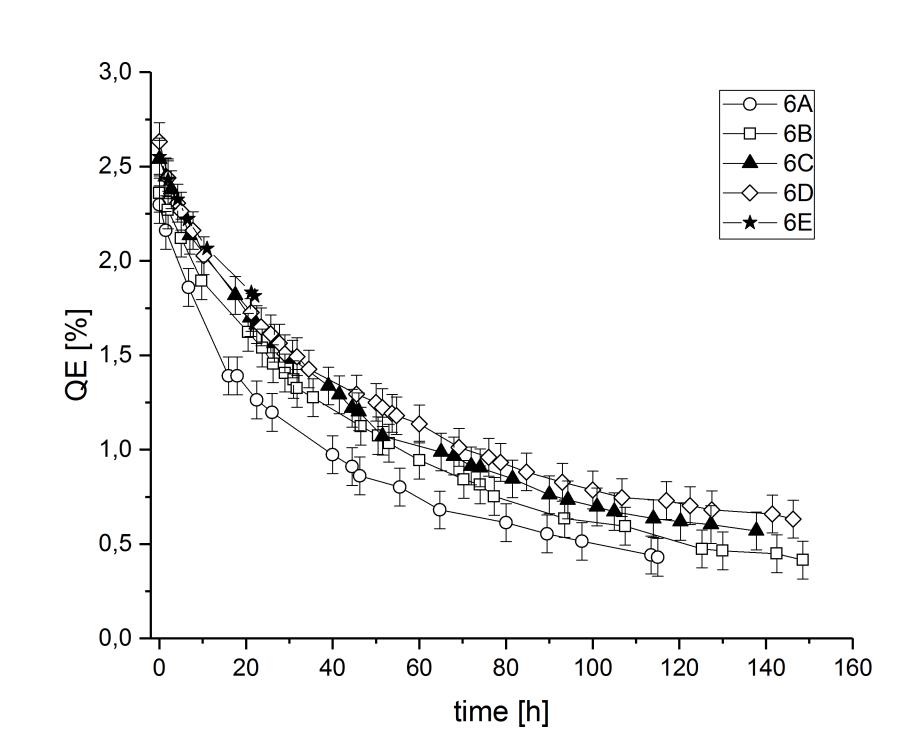


Fig. 4: QE tracking from GaN on silicon

### SEM Image

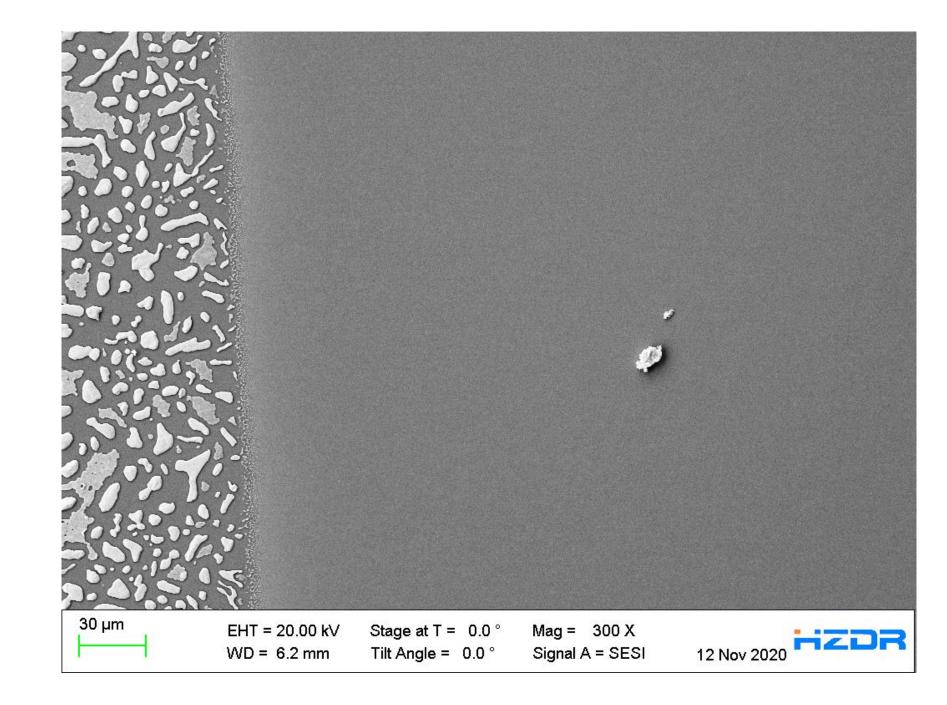


Fig. 5: SEM image of used GaN on silicon

#### GaN on sapphire

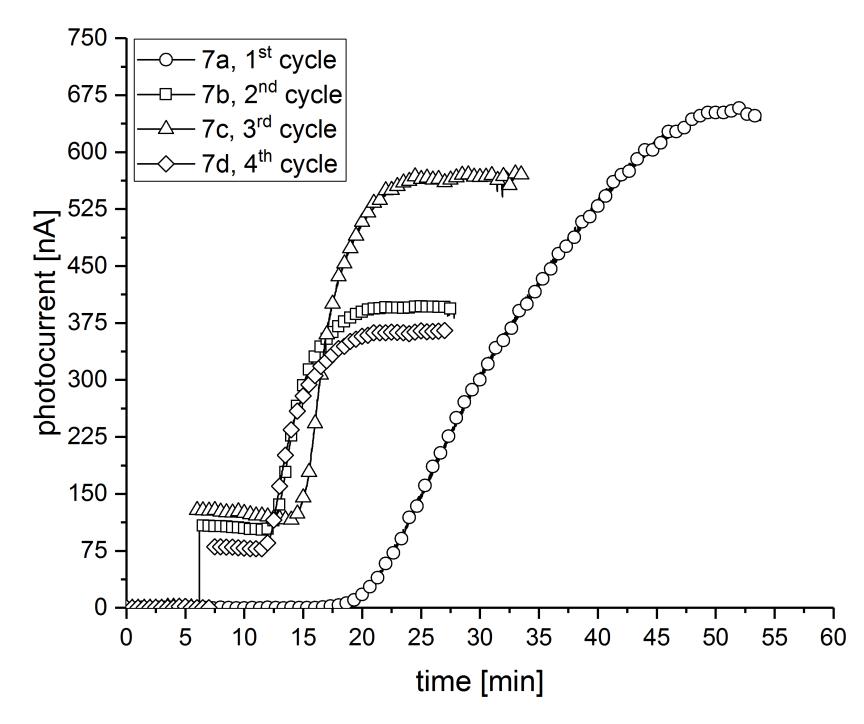


Fig. 6: photocurrent activation curves for GaN on sapphire

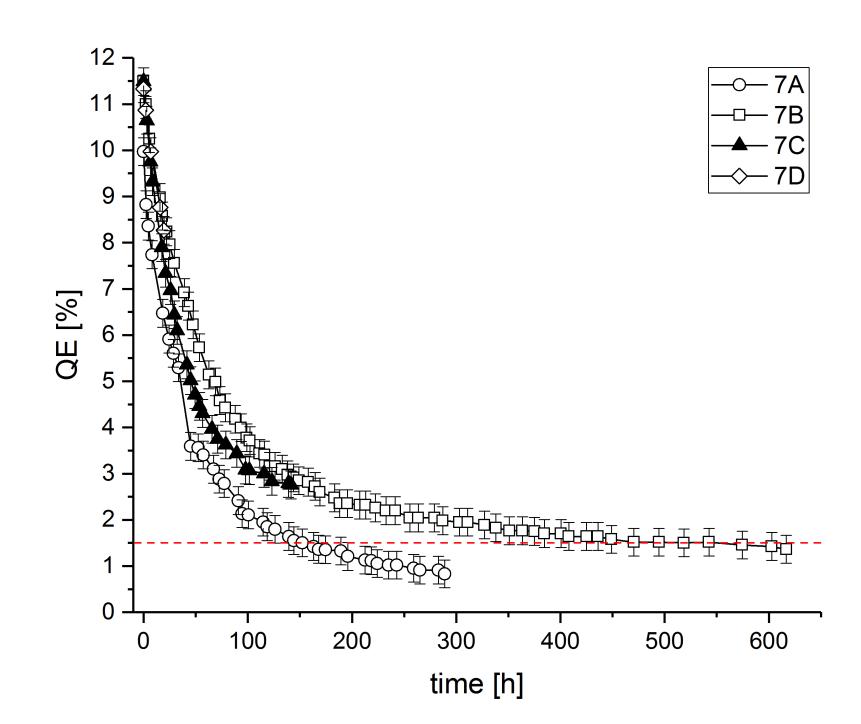


Fig. 7: QE tracking of GaN on sapphire

#### QE Comparison

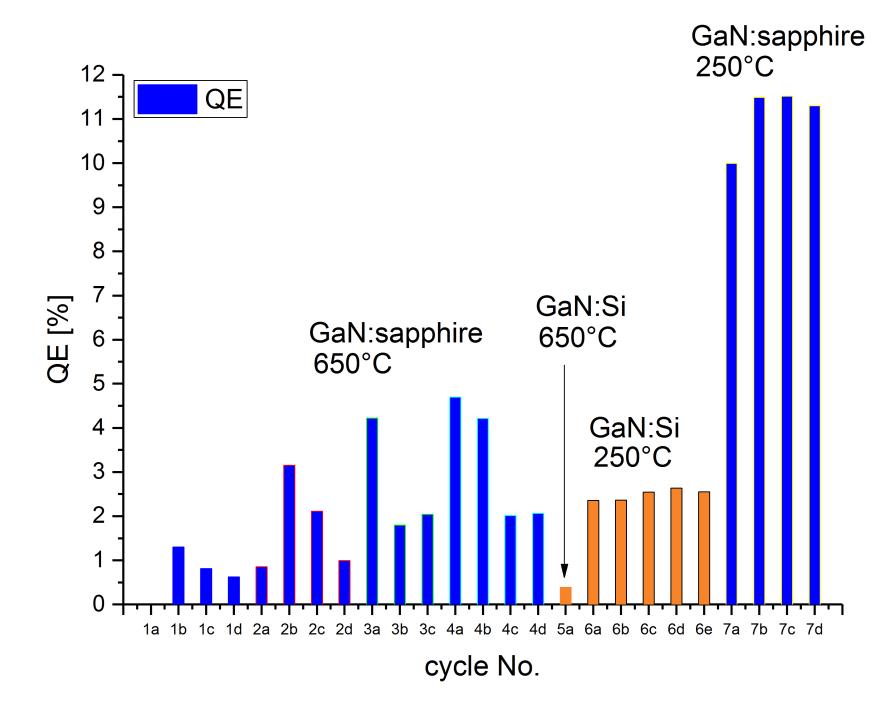
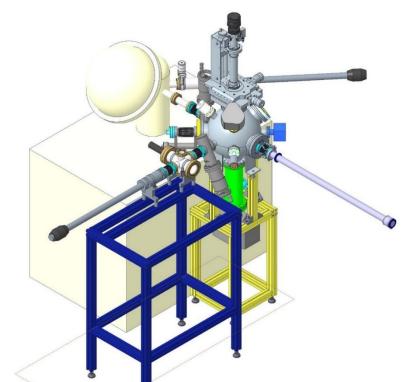


Fig. 8: QE comparison of all activated GaN samples

## Outlook

Activation of GaN with caesium and lifetime observation

- on other substrate (SiC)
- use better conductive samples (gold sputtering)
- compare to selfmade GaN (Uni Siegen)



Connection from activation chamber to XPS chamber to do qualitative and quantitative analysis

Fig. 9: combination of GaN chamber and XPS

## Acknowledgement

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<sup>&</sup>lt;sup>2</sup> Technical University Dresden, Dresden, Germany